Claims

1. A sputtering target comprising:

a forged aluminum or aluminum alloy material having an average grain size between 15 and 55 microns, the aluminum or aluminum alloy material having at least two of the following:

a homogeneous texture with minimal texture banding as measured by a banding factor B below 0.01;

a texture gradient H of less than 0.2; or

either weak (200) texture or near random texture characterized by a maximum intensity of inverse pole figure less than 3 times random in multiple directions.

2. The sputtering target of claim 1, wherein the aluminum or aluminum alloy material has a either weak (200) texture or near random texture in multiple directions, along planes parallel to a top face of the target and thickness planes perpendicular to the top face.

3. The sputtering target of either of claims 1 or 2, wherein the aluminum or aluminum alloy material has a banding factor B below 0.005.

4. The sputtering target of any of claims 1-3, wherein the aluminum or aluminum alloy material has a texture gradient H less than 0.12.

5. The sputtering target of any of claims 1-4, wherein the aluminum or aluminum alloy material has a uniform average grain size distribution between 20 microns and 45 microns.